

Table S1 A summary of various MXenes and their electrochemical performances as LIBs anode materials. (\*) denotes the binder-free.

Materials	Preparation	Current density/ Capacity/ Number of cycles	Voltage window	Configuration	Ref.
Multi-layered $\text{Ti}_2\text{CT}_x$	Immersion of $\text{Ti}_2\text{AlC}$ in 10 % HF at RT for 10 h	1 C, 110 mAh g <sup>-1</sup> , 80; 10 C, 70 mAh g <sup>-1</sup> , 200	0.05 to 2.5 V	Half-cell	154
$\text{TiO}_2/\text{Ti}_2\text{CT}_x$	Immersion of HF-etched multi-layered $\text{Ti}_2\text{CT}_x$ in 30 wt. % $\text{H}_2\text{O}_2$ for 5 min	100 mA g <sup>-1</sup> , 389 mAh g <sup>-1</sup> , 50; 500 mA g <sup>-1</sup> , 337 mAh g <sup>-1</sup> , 100; 1000 mA g <sup>-1</sup> , 280 mAh g <sup>-1</sup> , 1000	0.005 to 3.0 V	Half-cell	68
$\text{Cu}_2\text{O}/\text{Ti}_2\text{CT}_x$	Hydrothermal synthesis of HCl/LiF-prepared $\text{Ti}_2\text{CT}_x$ with stoichiometric amount of $\text{Cu}(\text{CH}_3\text{COO})_2 \cdot \text{H}_2\text{O}$ at 150 °C for 10 h	1000 mA g <sup>-1</sup> , 143 mAh g <sup>-1</sup> , 250	0.05 to 2.5 V	Half-cell	155
Free-standing “paper” of $\text{Ti}_3\text{C}_2\text{T}_x^*$	Typical HF etching, followed by DMSO-intercalation, sonication and filtration	1C, 410 mAh g <sup>-1</sup> , 700; 36 C, 110 mAh g <sup>-1</sup> , 700	0 to 2.5 V	Half-cell	31
Free-standing disc of 90 wt. % $\text{Ti}_3\text{C}_2\text{T}_x/\text{CB}^*$	Immersion of $\text{Ti}_3\text{AlC}_2$ in 50 % HF at RT for 18 h, $\text{Ti}_3\text{C}_2\text{T}_x$ powders cold pressed at 1 GPa	C/3 (30 mA g <sup>-1</sup> ), 97 mAh g <sup>-1</sup> , 5.9 mAh cm <sup>-2</sup> (areal capacity), 50	0.005 to 3.0 V	Half-cell	156
Porous 90 wt. % $\text{Ti}_3\text{C}_2\text{T}_x/$ MWCNTs*	Filtration of mixture of acid treated, partial oxidized HCl/LiF-prepared $\text{Ti}_3\text{C}_2\text{T}_x$ as catalysed by $\text{Cu}^{2+}$ , and MWCNTs	160 mA g <sup>-1</sup> , ca. 800 mAh g <sup>-1</sup> , 350	0.01 to 3.0 V	Half-cell	75
86.2 wt. % $\text{Ti}_3\text{C}_2\text{T}_x/\text{CNFs}$	Liquid-phase impregnation of HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ with PVP: $\text{Co}(\text{NO}_3)_2$ (mass ratio-1: 10), followed by CVD at 600°C for 0.5 h in Ar with acetylene	320 mA g <sup>-1</sup> , 320 mAh g <sup>-1</sup> , 300; 100 C, 97 mAh g <sup>-1</sup> , 2900	0.01 to 3.0 V	Half-cell	58
PVP-Sn(IV)@ $\text{Ti}_3\text{C}_2\text{T}_x$	Intercalation of HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ with LiOH, followed by immersion in 1 M $\text{SnCl}_4$ with 0.1g of PVP at RT for 24 h then dried	500 mA g <sup>-1</sup> , 544 mAh g <sup>-1</sup> , 200	0.01 to 3.0 V	Half-cell	59
90 wt.% $\text{Ti}_3\text{C}_2\text{T}_x/\text{Ag}$	Direct reduction of 50 mg of $\text{AgNO}_3$ in the presence of 100 mg of HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ and 100 mL of DI water	1 C (320 mA g <sup>-1</sup> ), 310 mAh g <sup>-1</sup> , 800; 10 C, 260 mAh g <sup>-1</sup> , 1000 50 C, 150 mAh g <sup>-1</sup> , 5000	0.01 to 3.0 V	Half-cell	78

Table S1 Continued.

Materials	Preparation	Current density/ Capacity/ Number of cycles	Voltage window	Configuration	Ref.
Free-standing film of 50 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /planar $\text{NiCo}_2\text{O}_4$	Alternatively spray coating of delaminated HCl/LiF $\text{Ti}_3\text{C}_2\text{T}_x$ and $\text{NiCo}_2\text{O}_4$ dispersions	1 C, 1010 mAh g <sup>-1</sup> , 100	0.01 to 3.0 V	Half-cell	157
Multi-layered $\text{Nb}_2\text{CT}_x$	Immersion of $\text{Nb}_2\text{AlC}$ in 50 % HF at RT for 90 h	1 C, 170 mAh g <sup>-1</sup> , 150; 10 C, 110 mAh g <sup>-1</sup> , 150	0 to 2.5 V	Half-cell	15
Free-standing film of 90 wt. % $\text{Nb}_2\text{CT}_x/\text{MWCNTs}$ *	Immersion of $\text{Nb}_2\text{AlC}$ in 50 % HF at 55 °C for 48 h, R- $\text{NH}_3^+$ intercalation, sonication; filtration of mixture of delaminated HF- etched $\text{Nb}_2\text{CT}_x$ and MWCNTs	0.5 C, 420 mAh g <sup>-1</sup> , 100; 2.5 C, 430 mAh g <sup>-1</sup> , 300; 10 C, ca. 220 mAh g <sup>-1</sup> , 100	1.0 to 3.0 V	Half-cell	47
Free-standing disc of 90 wt. % $\text{Nb}_2\text{CT}_x/\text{CB}^*$	Immersion of $\text{Nb}_2\text{AlC}$ in 50 % HF at 55 °C for 40 h, $\text{Nb}_2\text{CT}_x$ powders cold pressed at 1 GPa	30 mA g <sup>-1</sup> , 128 mAh g <sup>-1</sup> , 6.7 mAh cm <sup>-2</sup> (areal capacity), 50	0.005 to 3.0 V	Half-cell	156
Free-standing “paper” of 90 wt. % $\text{Nb}_2\text{CT}_x$ - MWCNTs	Immersion of $\text{Nb}_2\text{AlC}$ in 50 % HF at 55 °C for 48 h, TBAOH-intercalation, sonication and filtration of mixture with MWCNTs	50 mA g <sup>-1</sup> , ca. 270 mAh g <sup>-1</sup> , 100	0.01 to 3.0 V	Half-cell	158
Free-standing “paper” of 90 wt. % $\text{Nb}_2\text{CT}_x$ - MWCNTs*	As above	250 mA g <sup>-1</sup> , ca. 27 mAh g <sup>-1</sup> , 540	0.01 to 3.0 V	Full-cell (with lithiated graphite as anode)	158
Free-standing “paper” of 90 wt. % $\text{Nb}_2\text{CT}_x$ - MWCNTs*	As above	250 mA g <sup>-1</sup> , ca. 12 mAh g <sup>-1</sup> , 540	3.3 to 0.3 V	Full-cell (with pre-cycled $\text{LiFePO}_4$ as cathode)	158
Free-standing “paper” of 90 wt. % $\text{Nb}_2\text{CT}_x$ - MWCNTs*	As above	250 mA g <sup>-1</sup> , ca. 20 mAh g <sup>-1</sup> , 940	0.01 to 3.0 V	Full symmetrical cell	158
$\text{Nb}_2\text{O}_5$ @multi- layered $\text{Nb}_4\text{C}_3\text{T}_x$	Partial oxidation of HF- etched $\text{Nb}_4\text{C}_3\text{T}_x$ at 850 °C for 0.5 h under $\text{CO}_2$ flow rate of 75 sccm	0.25 C, 195 mAh g <sup>-1</sup> , 400	0.05 to 2.0 V	Half-cell	63

Table S1 Continued.

Materials	Preparation	Current density/ Capacity/ Number of cycles	Voltage window	Configuration	Ref.
Multi-layered $V_2CT_x$	Immersion of $V_2AlC$ or attrition-milled $V_2AlC$ in 50 % HF at RT for 90 h or 8 h respectively	1 C, 210 to 260 mAh g <sup>-1</sup> , 150; 10 C, 125 mAh g <sup>-1</sup> , 150	0 to 3.0 V	Half-cell	15
Free-standing “paper” of $Mo_2TiC_2T_x^*$	Immersion of $Mo_2TiAlC_2$ in 50 % HF at 55 °C for 48 h, DMSO-intercalation, sonication and filtration	1 C, 145 mAh g <sup>-1</sup> , 160	0.02 to 3.0 V	Half-cell	17
Free-standing “paper” of 92 wt. % $Mo_2CT_x$ - MWCNTs*	Immersion of $Mo_2Ga_2C$ in 14M HF at 55 °C for 6.6 days, TBAOH-intercalation, sonication and alternating filtration with MWCNTs	5 A g <sup>-1</sup> , 250 mAh g <sup>-1</sup> , 1000; 10 A g <sup>-1</sup> , 76 mAh g <sup>-1</sup> , 1000	0.005 to 3.0 V	Half-cell	32

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Table S2 A summary of various MXenes and their electrochemical performances as supercapacitor electrodes.

Materials	Preparation	Volumetric capacitance, Gravimetric capacitance	Scan rate or current density	Voltage window	Configuration	Ref.
Delaminated $\text{Ti}_3\text{C}_2\text{T}_x$	Immersion of $\text{Ti}_3\text{AlC}_2$ 6 M in HCl with LiF added, at 40 °C for 45 h	900 F cm <sup>-3</sup> , 245 F g <sup>-1</sup>	2 mV s <sup>-1</sup>	-0.3 to 0.25 V	Three-electrode system, activated carbon counter electrode, Ag/AgCl/1 M KCl reference electrode, 1 M $\text{H}_2\text{SO}_4$ electrolyte	30
Delaminated $\text{Ti}_3\text{C}_2\text{T}_x$	Typical HF etching, followed by DMSO-intercalation, sonication	520 F cm <sup>-3</sup> , 325 F g <sup>-1</sup> ; 415 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 5 A g <sup>-1</sup>	-0.4 to 0.2 V	As above	80
Delaminated $\text{Ti}_3\text{C}_2\text{T}_x$	Typical HF etching, followed by DMSO-intercalation, sonication	360 F cm <sup>-3</sup> ; 162 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup> <sup>1</sup>	-0.8 to 0.1 V	Three-electrode system, activated carbon counter electrode, Ag/AgCl/1 M KCl reference electrode, 1 M $\text{MgSO}_4$ electrolyte	55
Mixed 95 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /SWCNTs	Filtration of mixture of delaminated HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ and SWCNTs	300 F cm <sup>-3</sup> ; 236 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup> <sup>1</sup>	-0.8 to 0.1 V	As above	55
Sandwich-like 95 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /SWCNTs	Alternating filtration of delaminated HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ and SWCNTs dispersions	390 F cm <sup>-3</sup> ; 280 F cm <sup>-3</sup> ; 345 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup> <sup>1</sup> ; 5 A g <sup>-1</sup>	-0.8 to 0.1 V	As above	55
Mixed 95 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /MWCNTs	Filtration of mixture of delaminated HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ and MWCNTs	366 F cm <sup>-3</sup> ; 236 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup> <sup>1</sup>	-0.8 to 0.1 V	As above	55

Table S2 Continued.

Materials	Preparation	Volumetric capacitance, Gravimetric capacitance	Scan rate or current density	Voltage window	Configuration	Ref.
Sandwich-like 95 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /MWCNTs	Alternating filtration, with MWCNTs dispersion used instead	321 F cm <sup>-3</sup> ; 250 F cm <sup>-3</sup> ; 350 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup> ; 10 A g <sup>-1</sup>	-0.8 to 0.1 V	As above	55
Sandwich-like 95 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /onion-like carbon (OLC)	Alternating filtration, with OLC dispersion used instead	397 F cm <sup>-3</sup> ; 218 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup>	-0.8 to 0.1 V	As above	55
Sandwich-like 95 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /rGO	Alternating filtration, with rGO dispersion used instead	435 F cm <sup>-3</sup> ; 320 F cm <sup>-3</sup> ; 370 F cm <sup>-3</sup>	2 mV s <sup>-1</sup> ; 200 mV s <sup>-1</sup> ; 10 A g <sup>-1</sup>	-0.8 to 0.1 V	As above	55
92 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /PPy	Filtration of mixture of HCl/LiF-prepared $\text{Ti}_3\text{C}_2\text{T}_x$ and PPy	1000 F cm <sup>-3</sup> , 416 F g <sup>-1</sup>	5 mV s <sup>-1</sup>	-0.2 to 0.35 V	Three electrode system, activated carbon counter electrode, Ag/AgCl reference electrode, 1 M $\text{H}_2\text{SO}_4$ electrolyte	56
64.3wt. % PPy/ $\text{Ti}_3\text{C}_2\text{T}_x$	Electrophoretic deposition of HF-etched $\text{Ti}_3\text{C}_2\text{T}_x$ , electrochemically polymerization of PPy	291 F cm <sup>-3</sup> , 485 F g <sup>-1</sup>	1 mA cm <sup>-2</sup>	0.0 to 0.5 V	Three electrode system, saturated calomel reference electrode, 0.5 M $\text{H}_2\text{SO}_4$ electrolyte	162
$\text{Ti}_3\text{C}_2\text{T}_x$ EMI-TFSI ionogel film	Filtration of mixture of HCl/LiF-prepared $\text{Ti}_3\text{C}_2\text{T}_x$ , then immerse I Eml-TFSI electrolyte	62 F g <sup>-1</sup>	20 mV s <sup>-1</sup>	0.0 to 3.0 V	Two-electrode Swagelok symmetric cell, EMI-TFSI electrolyte	163
80 wt. % $\text{Ti}_3\text{C}_2\text{T}_x$ /MWCNTs	Filtration of mixture of HCl/LiF-prepared $\text{Ti}_3\text{C}_2\text{T}_x$ and MWCNTs	245 F cm <sup>-3</sup> , 85 F g <sup>-1</sup> ; 76 F g <sup>-1</sup>	2 mV s <sup>-1</sup> ; 1 A g <sup>-1</sup>	-0.4 to -0.2 V	Three-electrode system, activated carbon counter electrode, Ag wire reference electrode, 1 M EMITFSI in acetonitrile	164

## electrolyte

Table S2 Continued.

Materials	Preparation	Volumetric capacitance, Gravimetric capacitance	Scan rate or current density	Voltage window	Configuration	Ref.
Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> /MWCNTs	Filtration of mixture of delaminated HF-etched Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> and MWCNTs	393 F cm <sup>-3</sup>	5 mV s <sup>-1</sup>	0.1 to 0.55 V	Three-electrode system, platinum counter electrode, Hg/HgO reference electrode, 6 M KOH electrolyte	165
TiO <sub>2</sub> /HF-etched multi-layered Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub>	In situ hydrolysis of TBOT within mixture of HF-etched multi-layered Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> , heat treatment	143 F g <sup>-1</sup>	5 mV s <sup>-1</sup>	-1.0 to -0.35 V	Three-electrode system, platinum counter electrode, Ag/AgCl/3 M KCl reference electrode, 6 M KOH electrolyte	71
50 wt. % $\epsilon$ -MnO <sub>2</sub> /Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub>	Impregnation of HF-etched Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> with MnSO <sub>4</sub> at 60 °C then oxidized with KMnO <sub>4</sub>	211 F g <sup>-1</sup> ; 212 F g <sup>-1</sup>	10 mV s <sup>-1</sup> ; 1 A g <sup>-1</sup>	0.0 to 0.7 V	Two-electrode symmetric cell, in 30 wt. % KOH electrolyte	166
MnO <sub>2</sub> /Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub>	Addition of Mn(NO <sub>3</sub> ) <sub>2</sub> and KMnO <sub>4</sub> to HF-etched Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> , followed by sintering at 300 °C for 3 h in N <sub>2</sub>	130 F g <sup>-1</sup>	5 mV s <sup>-1</sup>	-1.0 to -0.4 V	Three-electrode system, platinum counter electrode, Ag/AgCl/3 M KCl reference electrode, 6 M KOH electrolyte	167
38 wt. % delaminated HF-etched Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> /nickel-aluminium layered double hydroxide composite	Addition of Ni-containing parent solution, H <sub>3</sub> BO <sub>3</sub> and Al(NO <sub>3</sub> ) <sub>3</sub> to delaminated HF-etched Ti <sub>3</sub> C <sub>2</sub> T <sub>x</sub> , stirred for 48 h at 50 °C	1061 F g <sup>-1</sup> ; 556 F g <sup>-1</sup>	1 A g <sup>-1</sup> ; 10 A g <sup>-1</sup>	0.0 to 0.6 V	Three-electrode system, platinum counter electrode, saturated calomel reference electrode, 6 M KOH electrolyte	168

Table S2 Continued.

Materials	Preparation	Volumetric capacitance, Gravimetric capacitance	Scan rate or current density	Voltage window	Configuration	Ref.
All solid-state HCl/LiF etched $\text{Ti}_3\text{C}_2\text{T}_x$ (ca. 1 $\mu\text{m}$ ), with a PVA/ $\text{H}_2\text{SO}_4$ gel electrolyte	Sequential spray-coating HCl/LiF etched $\text{Ti}_3\text{C}_2\text{T}_x$ (3–6 $\mu\text{m}$ ) and HCl/LiF etched $\text{Ti}_3\text{C}_2\text{T}_x$ (1 $\mu\text{m}$ ), drip casting of PVA/ $\text{H}_2\text{SO}_4$ gel electrolyte	357 F $\text{cm}^{-3}$	20 mV $\text{s}^{-1}$	0 to 0.6 V	Two-electrode, symmetrical all solid-state HCl/LiF etched $\text{Ti}_3\text{C}_2\text{T}_x$ microsupercapacitors	169
Free-standing “paper” of delaminated HF-etched $\text{Mo}_2\text{TiC}_2\text{T}_x^*$	Immersion of $\text{Mo}_2\text{TiAlC}_2$ in 50 % HF at 55 °C for 48 h, DMSO-intercalation, sonication and filtration	413 F $\text{cm}^{-3}$	2 mV $\text{s}^{-1}$	-0.1 to 0.4 V	Three-electrode system, activated carbon counter electrode, Ag/AgCl/1 M KCl reference electrode, 1 M $\text{H}_2\text{SO}_4$ electrolyte	17
Free-standing “paper” of delaminated HF-etched $\text{Mo}_2\text{CT}_x^*$	Immersion of $\text{Mo}_2\text{Ga}_2\text{C}$ in 14M HF at 55 °C for 6.6 days, TBAOH-intercalation, sonication and filtration	196 F $\text{g}^{-1}$	2 mV $\text{s}^{-1}$	-0.30 to 0.30 V	Three-electrode system, activated carbon counter electrode, Ag/AgCl/1 M KCl reference electrode, 1 M $\text{H}_2\text{SO}_4$ electrolyte	32
Orthorhombic $\text{Nb}_2\text{O}_5$ /amorphous carbon/ $\text{Nb}_2\text{CT}_x$	Partial oxidation of HF-etched $\text{Nb}_2\text{CT}_x$ at 850 °C for 1 h in $\text{CO}_2$	275 F $\text{g}^{-1}$	5 mV $\text{s}^{-1}$	-1.95 to 0 V	Three-electrode system, activated carbon counter electrode, AgCl coated Ag wire as reference electrode, 1 M $\text{LiClO}_4/\text{EC}/\text{DMC}$ electrolyte	64

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